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Complete if Known

Application Number 09/996,446

Filing Date November 28, 2001

First Named Inventor Downey

Art Unit 2812 2829

Examiner Name NYA Hollington

Attorney Docket Number VRO-004.01

U.S. PATENT DOCUMENTS

Examiner Initials *	Cite No. ¹	Document Number	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
		Number - Kind Code ² (if known)			
J.M.H. ↓	AA	US-6,051,483	04-18-2000	Lee, et al.	
	AB	US- 4,490,183	12-25-1984	Scovell	
	AC	US- 4,303,455	12-01-1981	Splinter	

FOREIGN PATENT DOCUMENTS

Examiner Initials *	Cite No. ¹	Foreign Patent Document	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear	T ³
		Country Code ³ - Number ⁴ - Kind Code ⁵ (if known)				
J.M.H. ↓	AD	WO 01/71787 A1	09-27-2001	Felch, et al.		
	AE	EP 1 130 659 A1	05-09-2001	Tsai, et al.		

OTHER PRIOR ART -- NON PATENT LITERATURE DOCUMENTS

Examiner Initials *	Cite No. ¹	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T ²
J.M.H. ↓	AF	THOMPSON, K., Electromagnetic Induction Heating for Cold Wall Rapid Thermal Processing, 8 th International Conference on Advanced Thermal Processing of Semiconductors - RTP 2001, No. 7419519, 25 - 29 September 2001, pages 190-196, XP002248749, USA, Anchorage.	
	AG	FUKANO, T., Microwave Annealing for Low Temperature VLSI Processing, International Electron Devices Meeting, Washington, December 1 - 4, 1985, Washington, IEEE, US, December 1985 (1985-12), pages 224-227, XP000842652.	

Examiner
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